



Response Under 37 CFR §1.116  
Expedited Procedure  
Group Art Unit 1765

# 10/B  
NG  
up  
11/30/01

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION OF

ITO et al.

Group Art Unit: 1765

E/A

L.J.M.-E

12/1/2001

Appln. No.: 09/361,980

Examiner: L. Umez-Eronini

Filed: July 28, 1999

Title: METHOD OF ETCHING METALLIC THIN  
FILM ON THIN FILM RESISTOR

RECEIVED  
NOV 30 2001  
TC 1700

\* \* \* \* \*

November 27, 2001

AMENDMENT

Hon. Commissioner of Patents  
Box AF  
Washington, D.C. 20231

Sir:

In reply to the Final Office Action dated August 27, 2001, please enter the following  
amendments and remarks:

IN THE CLAIMS:

Please cancel claim 30 without prejudice or disclaimer and amend claim 19 as  
follows:

19. (Twice Amended) A method of etching a metallic film, comprising the steps  
of:  
forming a thin film resistor on a semiconductor substrate through an insulation layer  
interposed therebetween;

sup  
E,  
Bx